

## **Patent Abstracts of Japan**

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APPLICANT: HITACHI LTD;

INVENTOR :

TSUBOSAKI KUNIHIRO;

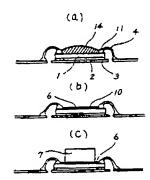
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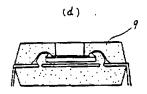
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TITLE

RESIN-SEALED SEMICONDUCTOR

DEVICE





ABSTRACT :

PURPOSE: To contrive improvement in resistance both to temperature cycling and to moisture of the title semiconductor device by a method wherein a transparent resin layer of a specific thickness is formed on the surface of the semiconductor element located on the circumference of a bonding wire by coating the solution, consisting of transparent resin and a low boiling point solvent, the solvent is removed, and the transparent resin is cured by heating.

CONSTITUTION: A solution 14, consisting of transparent resin and a low boiling point solvent, is dripped on the semiconductor element 1 attached to the island part 3 of a lead frame through a mounting member 2, the solution 14 is coated on the whole area of the surface 10 of the semiconductor element 1 and on a part of the ball part 11 of a bonding wire 4, and a transparent resin layer 6 of 1~300  $\mu m$  in thickness is formed on the surface 10 of the semiconductor element by removing the solvent by evaporation in the state wherein the coated material is left in the temperature of a room. Then, a transparent member 7 is provided thereon, the layer 6 is cured by heating, this structure is provided in a metal mold, sealing resin 9 is poured therein, the resin is cured by heating, it is picked out from the metal mold, the lead frame is cut and bent, and a semiconductor device is formed. As a result, the resistance to temperature cycling and the moisture resistance of the title semiconductor device can be improved by a simple process.

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